

EXPRESS MAIL NO. EL844534677US, MAILED 12/7/2001

M0635/7073

Sheet 1 of 6

Attenuating Phase Shift Mask for Photolithography

Inventor or Identifier: Rothschild, et al.

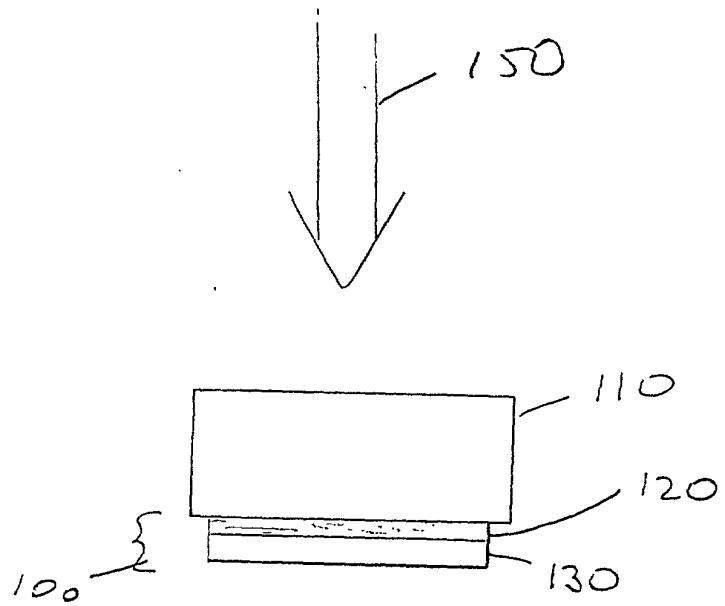


FIG. 1

EXPRESS MAIL NO. EL844534677US, MAILED 12/7/2001

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Sheet 2 of 6

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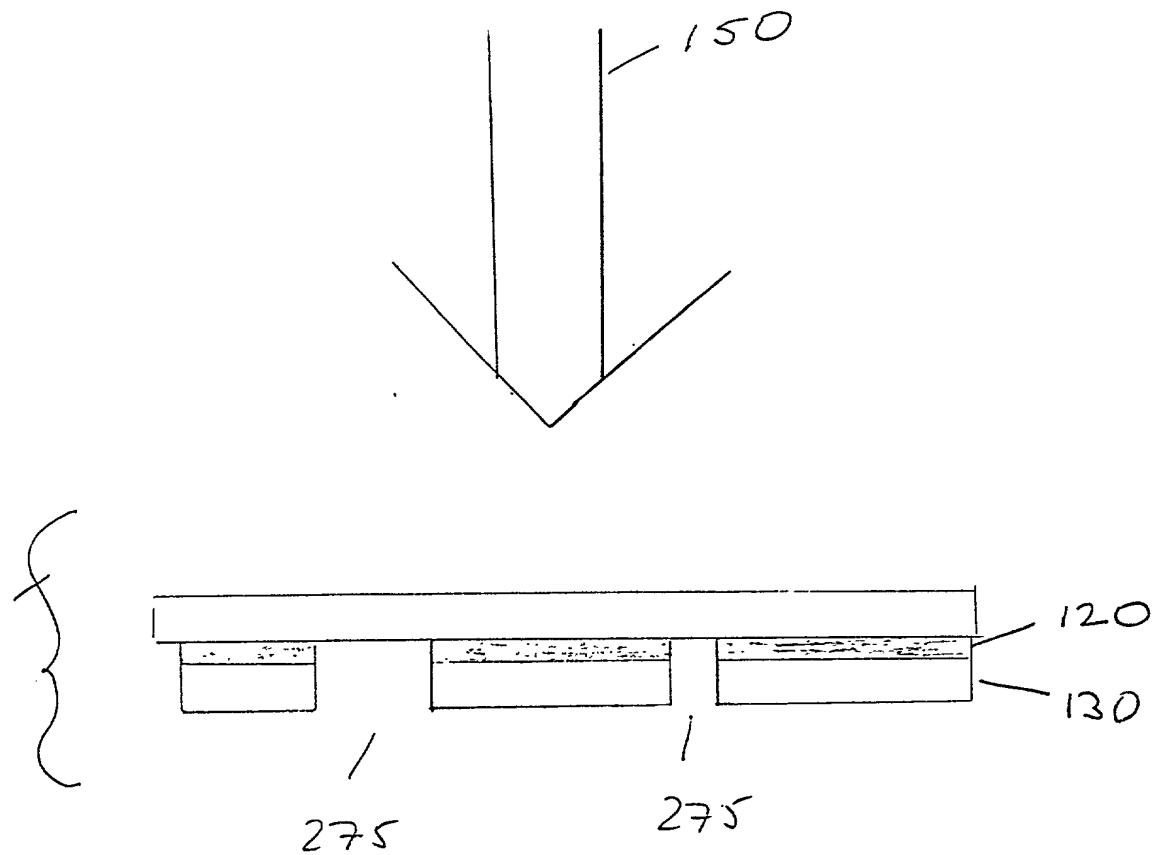


FIG. 2

EXPRESS MAIL NO. EL844534677US, MAILED 12/7/2001

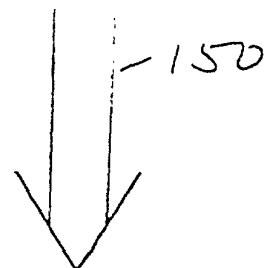
M0635/7073

Sheet 3 of 6

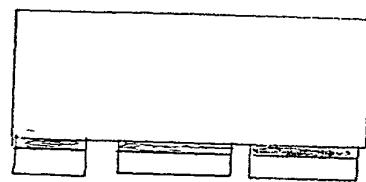
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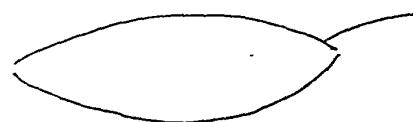
300



— 200



335



350



FIG. 3

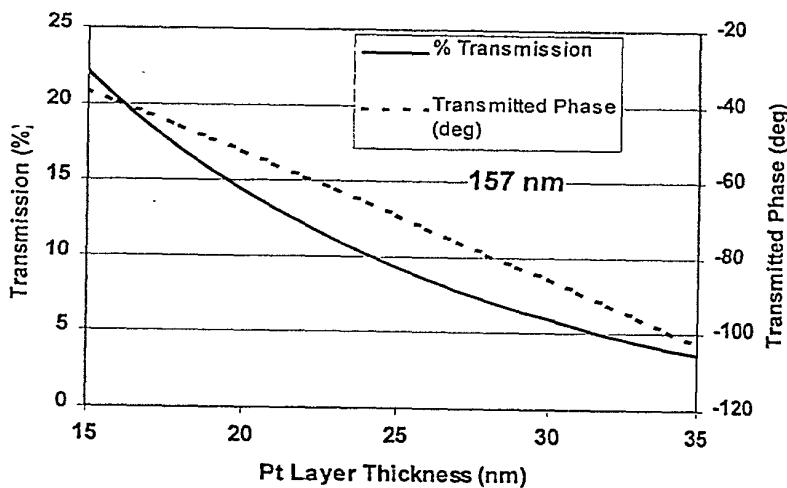


FIG 4a

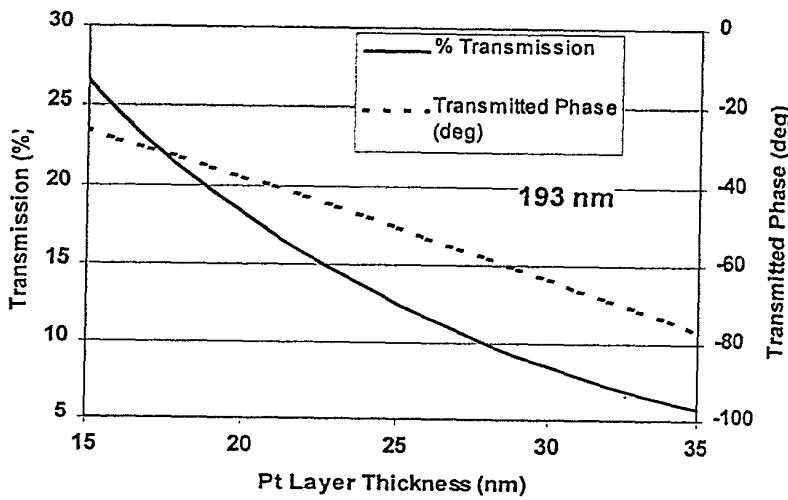


FIG 4b

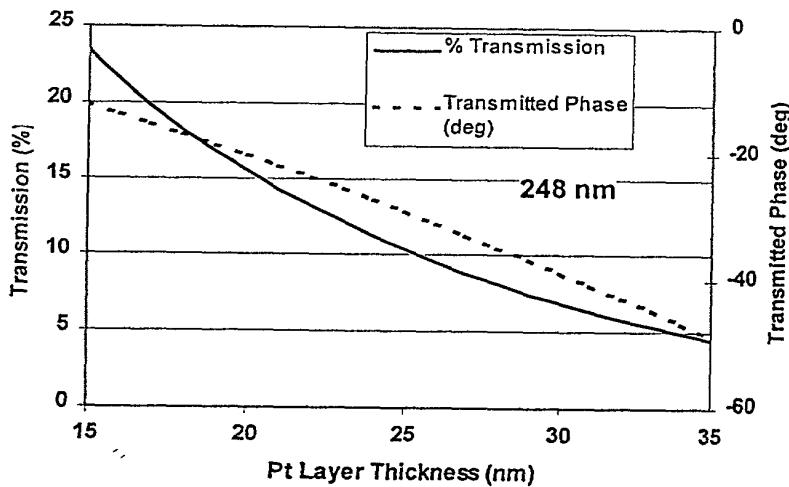


FIG 4c

500

4,002,004,2 1,230,304

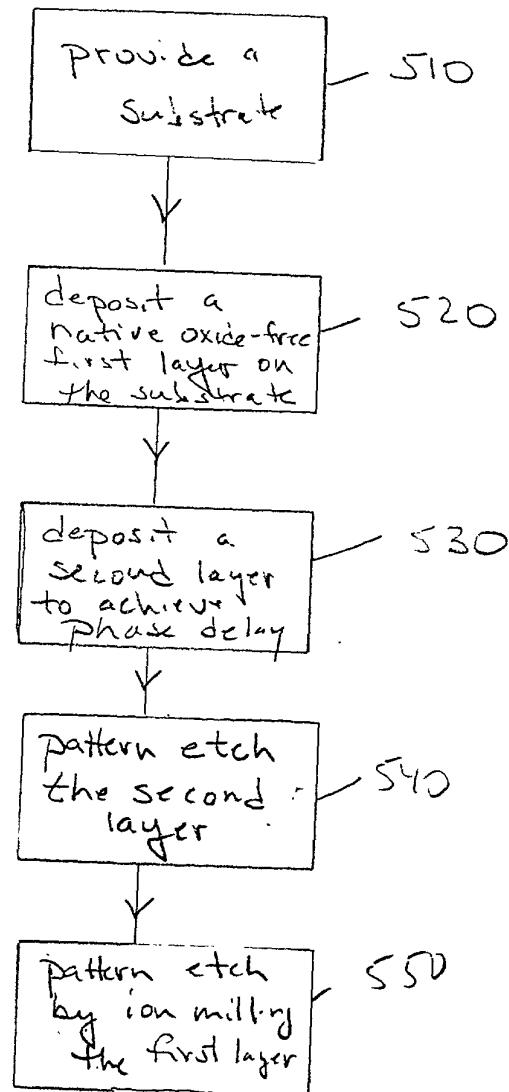


FIG 5a

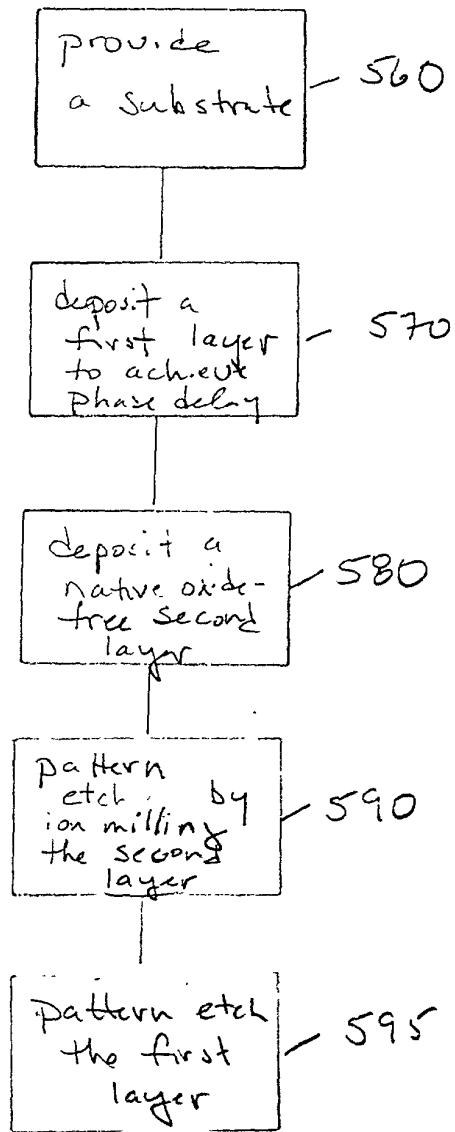
SSO

FIG 5b